

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1795
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE
Filed:	September 5, 2006	Dated:	October 13, 2009
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents  
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Dated: October 13, 2009

Signature: K.J. Goodhand/



**AMENDMENT AND RESPONSE PURSUANT TO 37 C.F.R. §1.111**

Sir:

This is in response to the Office Action dated July 10, 2009, the due date for which is October 10, 2009. As October 10, 2009 fell on a Saturday and the USPTO was closed on Monday, October 12, 2009 for a Federal Holiday, this response is timely filed on Tuesday, October 13, 2009. Please amend the above-identified application as follows:

**Amendments to the Claims** begin on page 2 of this submission.

**Remarks** begin on page 9 of this submission.